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(54) **SUPERCRITICAL FLUID TECHNOLOGY FOR CLEANING PROCESSING CHAMBERS AND SYSTEMS**

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(58) **Field of Classification Search** **134/1, 134/34, 26, 22.1, 1.3, 2; 438/905, 904**
See application file for complete search history.

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(57) **ABSTRACT**

The invention includes a method of cleaning a processing chamber by introducing supercritical fluid into the processing chamber. A residue over an internal chamber surface is contacted with the supercritical fluid to remove the residue from the surface. The invention also includes a method of removing deposited material from internal surfaces of a processing system. A cleaning agent comprising at least one of C₃H₈, C₂H₆ and CH₄ is provided in supercritical phase into at least a portion of the processing system. A material deposited on an internal surface of the processing system is contacted with the cleaning agent to remove at least a portion of the deposited material.

15 Claims, 2 Drawing Sheets

